

Electronic Supplementary Material

Ferroelectric-mediated filamentary resistive switching in P(VDF-TrFE)/ZnO nanocomposite films

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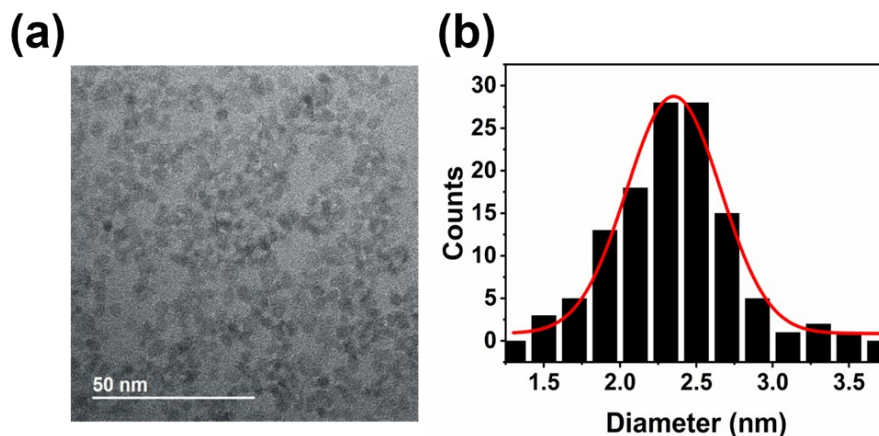


Figure S1. (a) TEM image of the as-synthesized ZnO NPs and (b) the corresponding particle size distribution

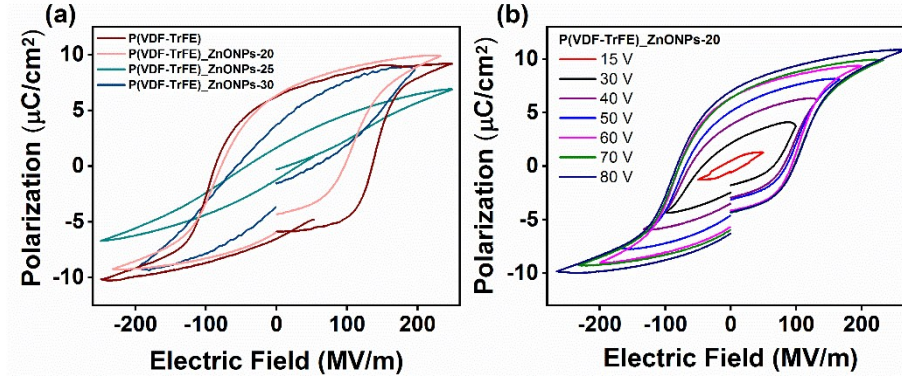


Figure S2. (a) P-E curves of P(VDF-TrFE)_ZnO NPs-20, P(VDF-TrFE)_ZnO NPs-25, and P(VDF-TrFE)_ZnO NPs-30 nanocomposites and (b) the PE loops of P(VDF-TrFE)_ZnONPS-20 nanocomposites at various applied voltages.

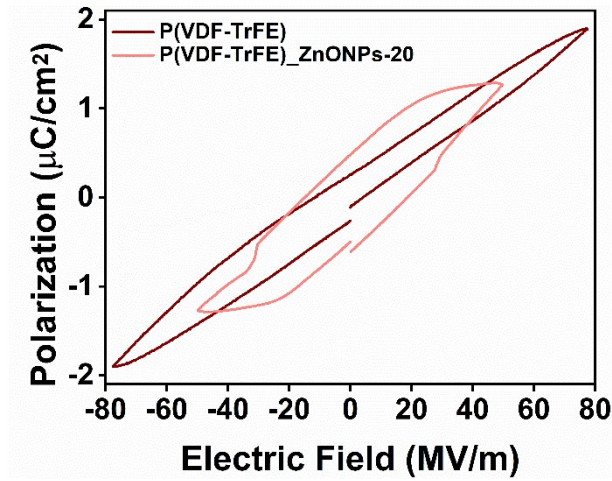


Figure S3. P-E curves of P(VDF-TrFE) and P(VDF-TrFE)_ZnO NPs-20 nanocomposites film recorded at 35 V, 15 V, respectively.

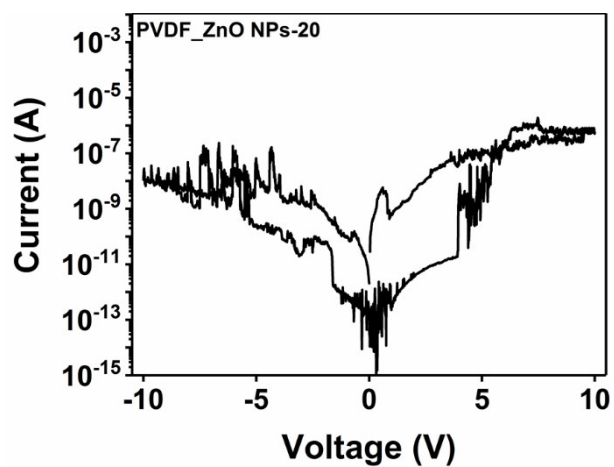


Figure S4. The *I*-*V* curves of Au/PVDF_ZnO NPs/n⁺⁺ Si device

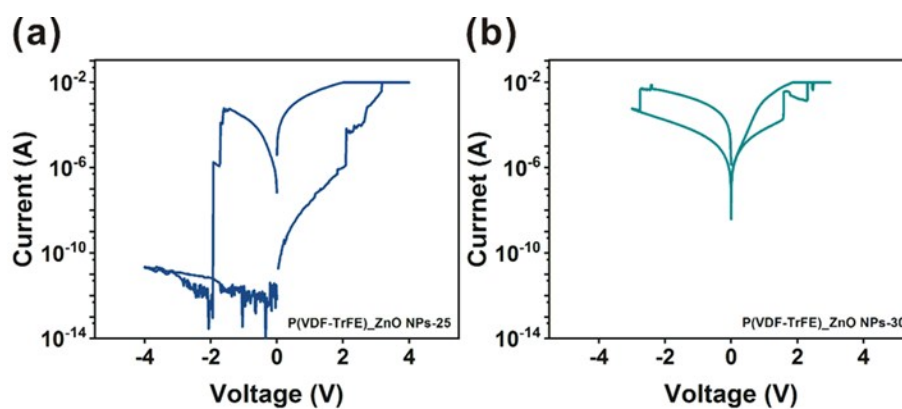


Figure S5. The *I*-*V* curves of (a) Au/P(VDF-TrFE)_ZnO NPs-25/n⁺⁺ Si and (b) Au/P(VDF-TrFE)_ZnO NPs-30/n⁺⁺ Si devices

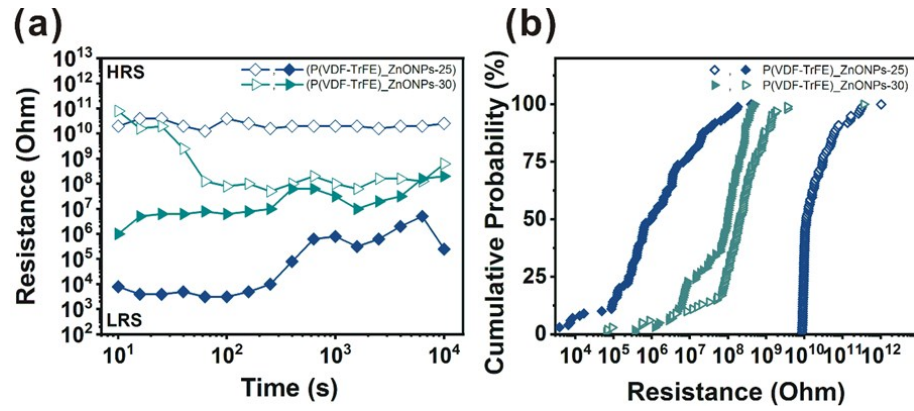


Figure S6. Electrical characterization of the Au/P(VDF-TrFE)_ZnO NPs-25/n⁺⁺Si and Au/P(VDF-TrFE)_ZnO NPs-30/n⁺⁺Si devices. (a) Stability of R_{HRS} and R_{LRS} through the retention test of the P(VDF-TrFE)_ZnO NPs devices. (b) Cumulative probability distributions of the resistance values at a read voltage of 0.5 V for the initial 10,000 cycles. The devices exhibit poor stability.

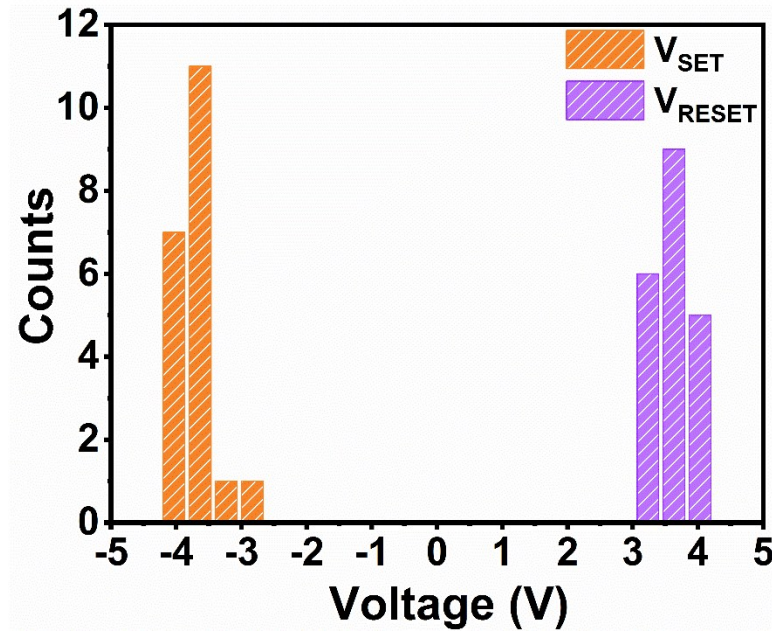


Figure S7. The cumulative probability of V_{SET} and V_{RESET} of 20 different Au/P(VDF-TrFE)_ZnONPs-20/n⁺⁺Si device.

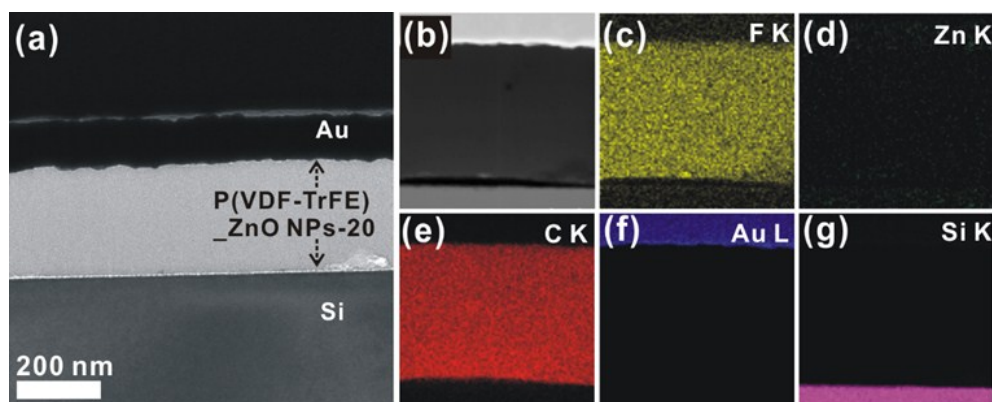


Figure S8. (a) Cross-sectional TEM image of unbiased Au/P(VDF-TrFE)_ZnO NPs-20/ n^{++} Si device. (b-g) STEM and EDS maps of the corresponding area. ZnO NPs are uniformly dispersed in the P(VDF-TrFE) matrix.

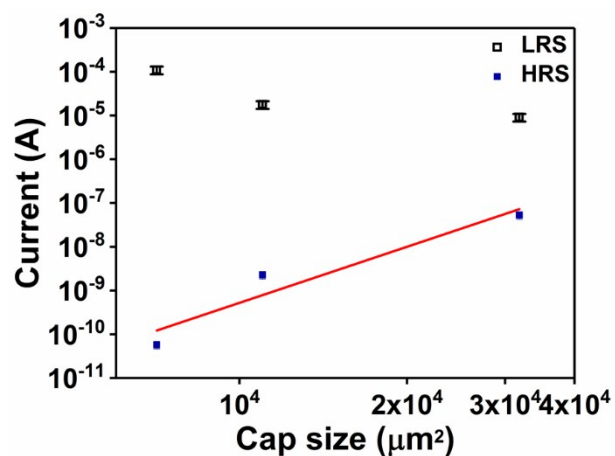


Figure S9. The dependence of cell resistance (HRS and LRS) with the various device area for identification whether the conduction occurs through localized filamentary channels.